

Title (en)

METHOD AND APPARATUS FOR COATING A SUBSTRATE IN A VACUUM

Title (de)

VERFAHREN UND VORRICHTUNG ZUM BESCHICHTEN EINES SUBSTRATES IM VAKUUM

Title (fr)

PROCEDE ET APPAREIL DESTINE AU DEPOT SOUS VIDE D'UN REVETEMENT SUR UN SUBSTRAT

Publication

**EP 1246951 A4 20041013 (EN)**

Application

**EP 00975328 A 20001020**

Priority

- US 0029099 W 20001020
- US 16109499 P 19991022

Abstract (en)

[origin: WO0131081A1] A method and apparatus for coating a substrate with a deposition material in a vacuum wherein a material source having a substantially longitudinal deposition emission component is used to create a substantially longitudinal material deposition emission plume which coats a surface of the substrate without increasing the throw distance between the substrate and the material source.

IPC 1-7

**C23C 14/24**; **C23C 14/12**

IPC 8 full level

**C23C 14/12** (2006.01); **C23C 14/24** (2006.01)

CPC (source: EP KR)

**C23C 14/12** (2013.01 - EP KR); **C23C 14/24** (2013.01 - KR); **C23C 14/243** (2013.01 - EP); **C23C 14/543** (2013.01 - KR)

Citation (search report)

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**WO 0131081 A1 20010503**; AU 1339401 A 20010508; CA 2388178 A1 20010503; CN 1175126 C 20041110; CN 1402800 A 20030312; DE 10085115 T1 20021107; EP 1246951 A1 20021009; EP 1246951 A4 20041013; JP 2003513169 A 20030408; KR 100495751 B1 20050617; KR 20020068039 A 20020824; TW 574396 B 20040201

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